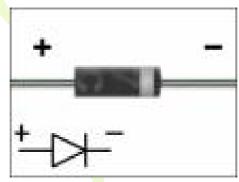
Lecture 02 Diodes



圖片來自;www.personeel.glr.nl/koster/elektro/diodes.JP



- Semiconductor physics
- Diode forward characteristic
- Diode reverse characteristic
- Special diodes

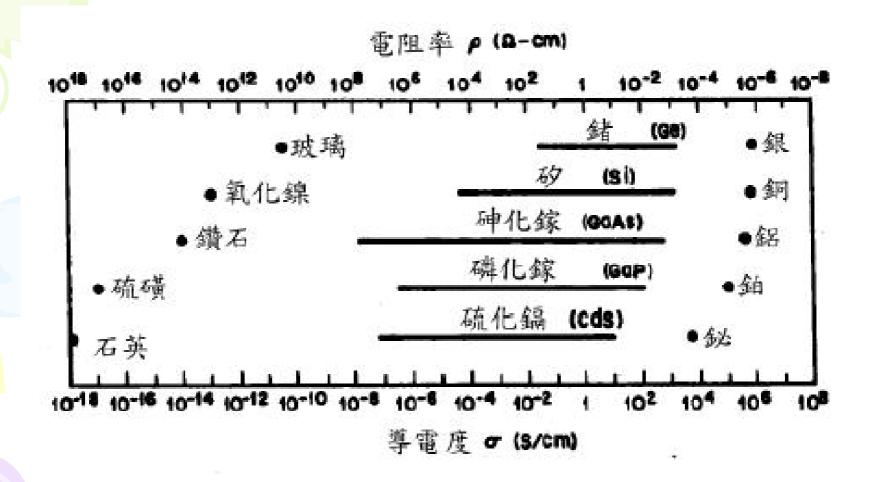
Solid-state material

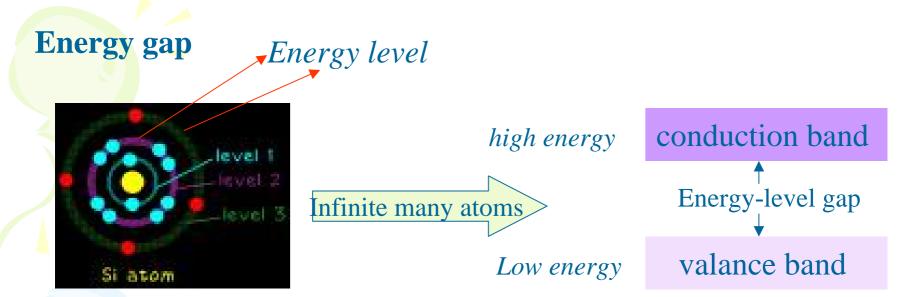
- Insulator (SiO2)
 - Strong covalent bonds, no free electron
 - Conductivity $\sigma < 10^{-8} (\Omega cm)^{-1}$
 - Energy gap $Eg \ge 3eV$

$$1eV \equiv 1.6 \times 10^{-19} Joule$$

eV: eletron voltage

- Semi-conductor (Si, Ge)
 - Conductivity $10^{-8} < \sigma < 10^{3} (\Omega cm)^{-1}$
 - Energy gap 0 < Eg < 3eV
- Conductor (Cu, Ag)
 - Weak covalent bonds, many free electrons
 - Conductivity $\sigma > 10^3 (\Omega cm)^{-1}$
 - Energy gap Eg = 0eV

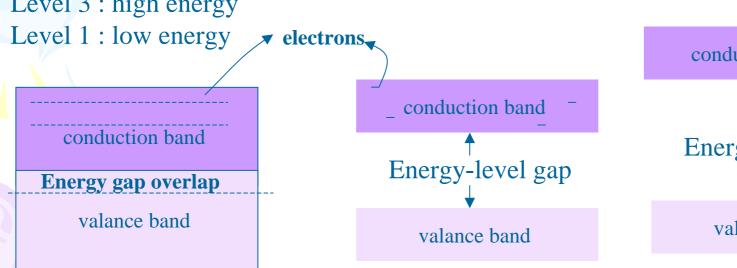


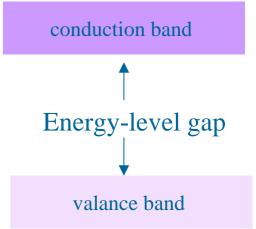


http://oldsite.vislab.usyd.edu.au/photonics/devices/semicdev/doping2.html



Level 3: high energy



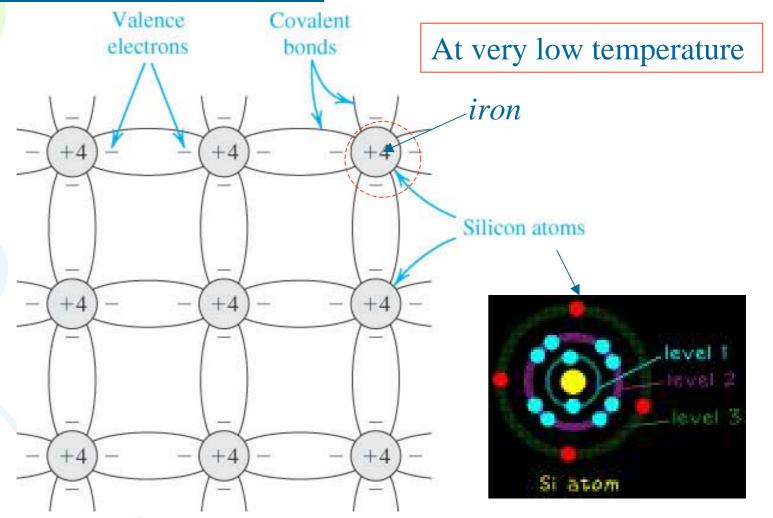


Famous Semi-conductors

- Element semi-conductor
 - Si
 - Cheap
 - Energy gap > Ge → small leakage current
 - Stable oxide
 - Ge
 - First transistor
 - Small energy gap
 - Unstable oxide
- Compound semi-conductor
 - GaAs

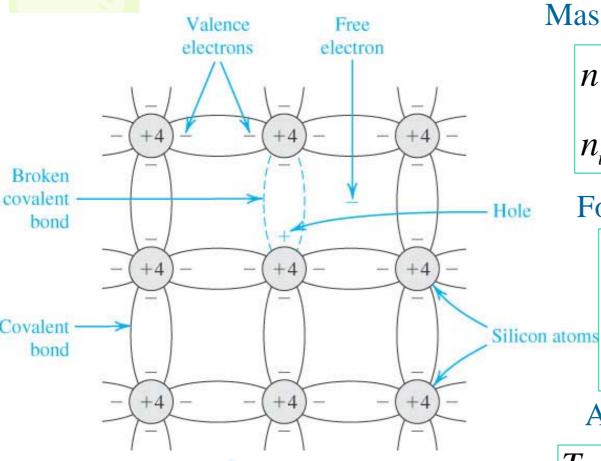
半導體種類		帶溝 Eg (eV)
鍺(Ge)	2.4×10 ¹³	0.67
전(Si)	1.45×10 ¹⁰	1.12
砷化鎵(GaAs)	1.79×10 ⁶	1.42

Intrinsic semiconductor (silicon)



http://oldsite.vislab.usyd.edu.au/photonics/devices/semicdev/doping2.html

Intrinsic semiconductor at room temperature



Free electrons and holes generated by thermal ionization, so the concentration is same $n = p = n_i$

Mass-action law:

$$n = p = n_i \Rightarrow np = n_i^2$$

$$n_i^2 = BT^3 e^{-\frac{E_G}{KT}}$$

For silicon semi-conductor

Material parameter
$$B = 5.4 \times 10^{31}$$

$$E_G = 1.12 eV$$
Boltzmann's constant $k = 8.62 \times 10^{-5}$ eV/ $_K$

At room temperature

$$T \approx 300K$$

$$n_i \approx 1.45 \times 10^{10} \frac{carriers}{cm^3}$$

Hole and electrons moving

1. drift

Drift velocity $v = \mu E$

Resistivity
$$R = \rho / A$$

Charge density
$$\rho \equiv nq(\Omega - cm)$$

conductivity
$$\sigma \equiv nq\mu$$

$$J = \sigma E$$

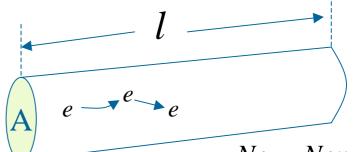
$$J_{p} = qp\mu_{p}E$$

$$J_{n} = qn\mu_{n}E$$

$$J_{drift} = q(p\mu_{p} + n\mu_{n})E$$

E: electric field strength (V/cm)

 μ : mobility of hole/electron (cm²/V-sec)



$$I \equiv \frac{Nq}{T} = \frac{Nqv}{L}$$

 $E = \frac{f}{f}$

$$J = \frac{I}{A} \Longrightarrow J = \frac{Nqv}{AL}$$

$$n \equiv \frac{N}{LA} \Longrightarrow J = nqv$$

Electron density

For intrinsic silicon:

$$\mu_p = 480 \, \text{cm}^2 / V \cdot s$$

$$\mu_n = 1350 \, cm^2 / V \cdot s$$

2. diffusion

$$J_{p} = -qD_{p} \frac{dp}{dx}$$
$$J_{n} = qD_{n} \frac{dn}{dx}$$

$$J_n = qD_n \frac{dn}{dx}$$

$$q = 1.6 \times 10^{-19} C$$

J: current density

q: electron charge

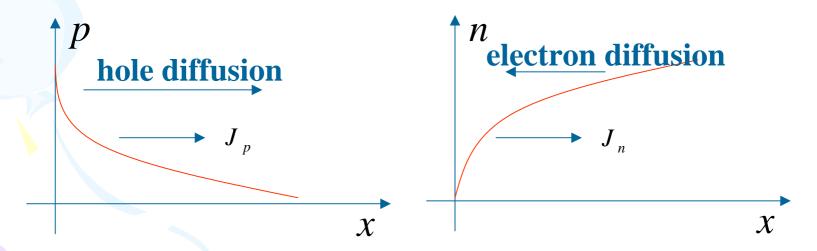
D : diffusivity of hole/electron

For intrinsic silicon:

$$D_p = 12 \frac{cm^2}{s}$$

$$D_n = 34 \frac{cm^2}{s}$$

$$D_n = 34 \, cm^2 / s$$

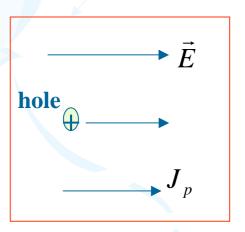


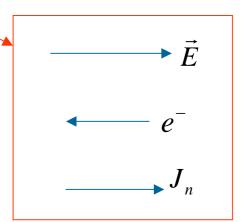
The conventional current direction is the positive charge flow direction

Currents in semi-conductor = drift current + diffusion current

$$J_{p} = pq\mu_{p}E - qD_{p}\frac{dp}{dx}$$

$$J_{n} = nq\mu_{n}E + qD_{n}\frac{dn}{dx}$$





Einstein relationship: relationship between drift current and diffusion current

$$\frac{D_n}{\mu_n} = \frac{D_p}{\mu_p} = V_T$$
 V_T thermal voltage 溫度伏特當量

$$V_T$$
 thermal voltage 溫度伏特當量

At room temperature $(20^{\circ}C)V_{T} \approx 25mV$

$$V_T \equiv \frac{kT}{q}$$

Boltzmann's constant
$$k = 1.38 \times 10^{-23} \text{ joules/kelvin}$$

$$T = 273 + {}^{o}C$$

 $q = 1.6 \times 10^{-19} coulomb$

$$T = 20^{\circ} C \rightarrow 293^{\circ} K \Rightarrow V_{T} \approx 25mV$$
$$T = 27^{\circ} C \rightarrow 300^{\circ} K \Rightarrow V_{T} \approx 26mV$$

Current in solid-state material

Insulator

$$J_T = 0$$

Semi-conductor

$$J_{p} = pq\mu_{p}E - qD_{p}\frac{dp}{dx}$$

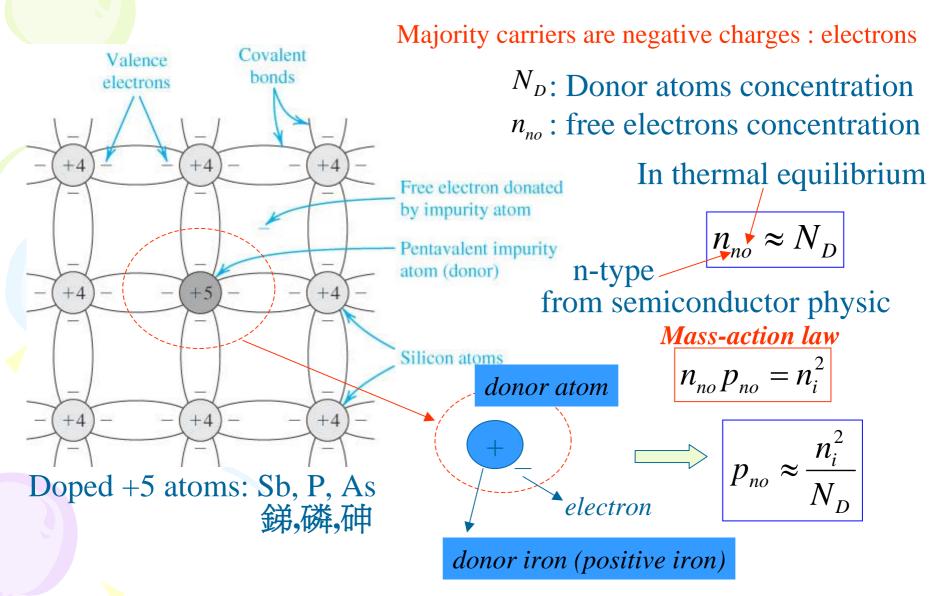
$$J_{T} = J_{p} + J_{n}$$

$$J_{n} = nq\mu_{n}E + qD_{n}\frac{dn}{dx}$$

Conductor

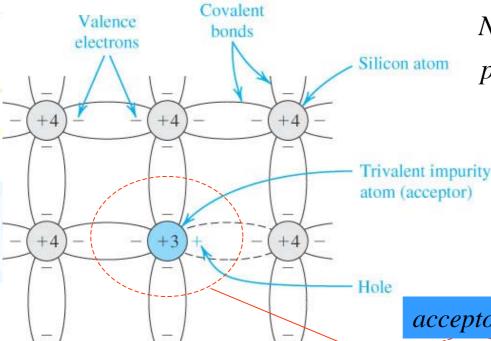
$$J_T = J_n = nq\mu_n E$$

N-type impure semiconductor (donor)



P-type impure semiconductor (acceptor)





+4

 N_A : Acceptor atoms concentration

 p_{vo} : free holes concentration

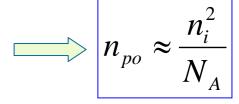
In thermal equilibrium

$$p_{po} \approx N_A$$

from semiconductor physic

acceptor atom

$$p_{po}n_{po}=n_i^2$$



Doped +3 atoms: B, Ga, In, 硼。镓。钢

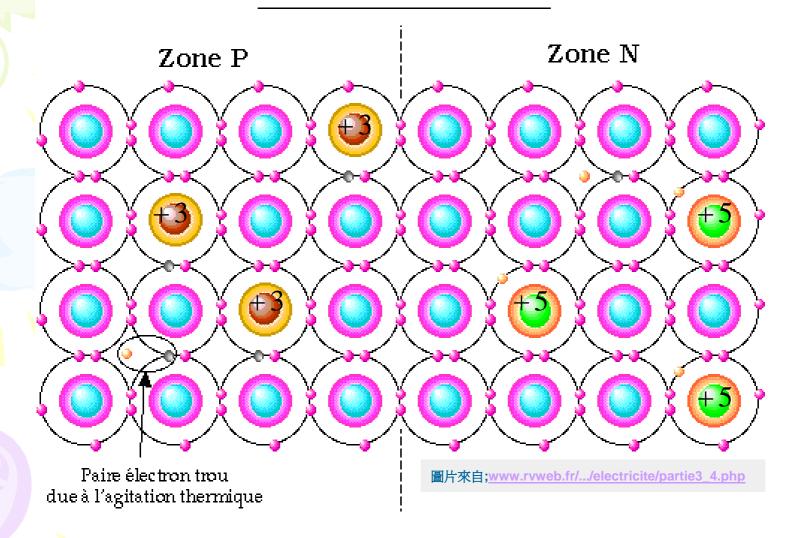
+4

acceptor iron (negative iron)

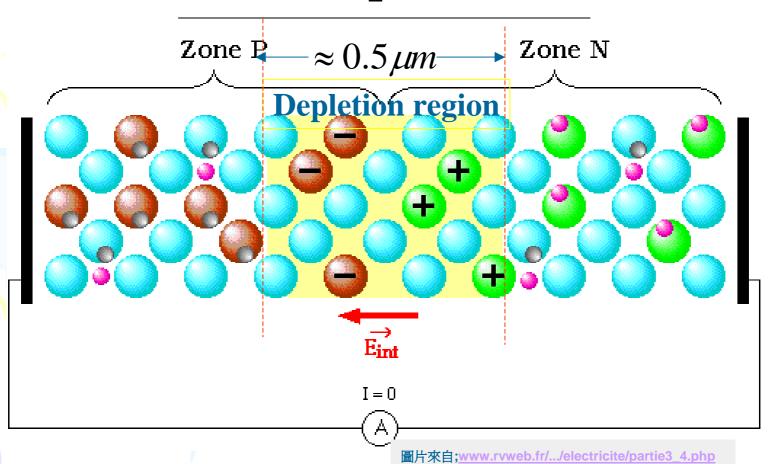
hole

+4

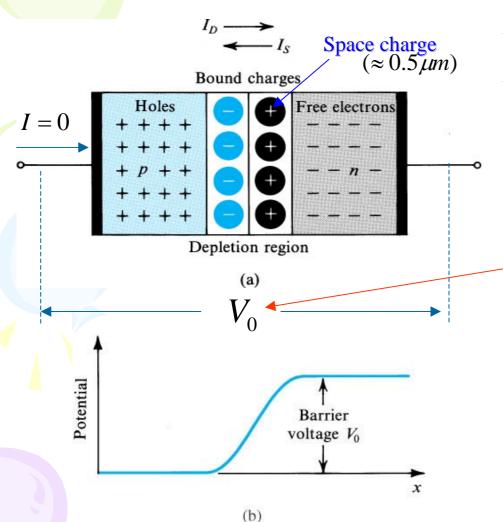
Jonction PN



Jonction PN sans champ extérieur



PN Junction under open-circuit



 I_D : Diffusion current

 I_s : Drift current

$$\therefore I = 0 \to I_D = I_S$$

Contact difference of potential

$$V_o = V_T \ln(\frac{N_A N_D}{n_i^2})$$

For silicon at room temperature

$$V_o = 0.6 \sim 0.8V$$

$$J_p = pq\mu_p E - qD_p \frac{dp}{dx}$$

$$J_n = nq\mu_n E + qD_n \frac{dn}{dx}$$

$$J_p = 0 \Rightarrow pq\mu_p E = qD_p \frac{dp}{dx}$$

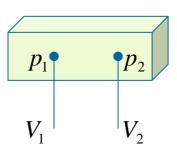
$$E = \frac{D_p}{p\mu_p} \frac{dp}{dx}$$

$$\therefore \frac{D_p}{\mu_p} = \frac{D_n}{\mu_n} = V_T$$

$$\Rightarrow E = \frac{V_T}{p} \frac{dp}{dx}$$

$$\therefore E = -\frac{dV}{dx}$$

$$\Rightarrow dV = -V_T \frac{dp}{p}$$



$$\int dV = \int -V_T \frac{1}{p} dp$$

$$\rightarrow V_2 - V_1 = -V_T (\ln p_2 - \ln p_1) = V_T \ln \frac{p_1}{p_2}$$

Boltzmann equation

nn equation
$$\frac{V_{21}}{\Rightarrow p_1 = p_2 e^{\frac{V_{21}}{V_T}}}$$

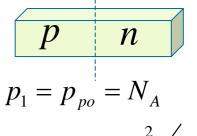
$$J_n = 0 \Rightarrow n_1 = n_2 e^{\frac{-V_{21}}{V_T}}$$
Mass-action law
$$n_1 p_1 = n_2 p_2 = n_i^2$$

$$n_1 p_1 = n_2 p_2 = n_i^2$$

$$V_o = V_{21} = V_T \ln \frac{p_1}{p_2}$$

$$V_o = V_T \ln \frac{N_A N_D}{n_i^2}$$

Microelectronic Circuit by meiling CHEN



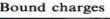
$$p_2 = p_{n0} = \frac{n_i^2}{N_D}$$

Depletion region

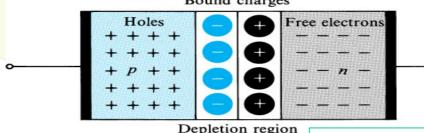


Bound charges





(a)



$\rho(x)$

Charge density

$$-qN_{_A}$$

 $-W_p$

 $-W_p$

E(x)

Field strength



Poisson equation

$$\nabla^2 V = -\frac{\rho}{\varepsilon}$$

$$\Rightarrow \frac{\partial^2 V}{\partial x^2} = -\frac{\rho(x)}{\varepsilon}$$

$$E(x) = \int_{-W_p}^{W_n} \frac{\rho(x)}{\varepsilon} dx$$

$$V(x) = -\int_{-W_p}^{W_n} E(x) dx$$

$$E_0 = -\frac{qN_AW_p}{\mathcal{E}} = -\frac{qN_DW_n}{\mathcal{E}}$$

$$V_0 = -\int_{-W_p}^{0} E(x)dx - \int_{0}^{W_n} E(x)dx$$

$$= \frac{qN_AW_p^2}{2\varepsilon} + \frac{qN_DW_n^2}{2\varepsilon}$$

 $|qN_AW_p = qN_DW_n|$

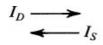
 qN_D

 W_n

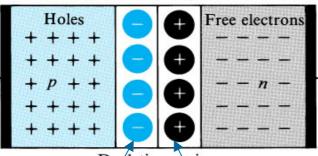
 W_n

 E_0

Depletion width



Bound charges



Depletion region



Charge equality

$$qW_pAN_A = qW_nAN_D$$

$$\Rightarrow \frac{W_n}{W_p} = \frac{N_A}{N_D}$$

$$\Rightarrow W_n N_D = W_p N_A$$

$$W = W_p + W_n \Rightarrow W = \frac{N_D}{N_A} W_n + W_n$$

$$\Rightarrow W_n = \frac{N_A}{N_A + N_D} W \Rightarrow W_p = \frac{N_D}{N_A + N_D} W$$

$$V_0 = \frac{q N_A W_p^2}{2\varepsilon} + \frac{q N_D W_n^2}{2\varepsilon}$$

$$V_0 = \frac{q}{2\varepsilon} \left(\frac{N_A N_D}{N_A + N_D}\right) W^2$$

$$W_{dep} = W_n + W_p = \sqrt{\frac{2\varepsilon_s}{q}(\frac{1}{N_A} + \frac{1}{N_D})V_0}$$

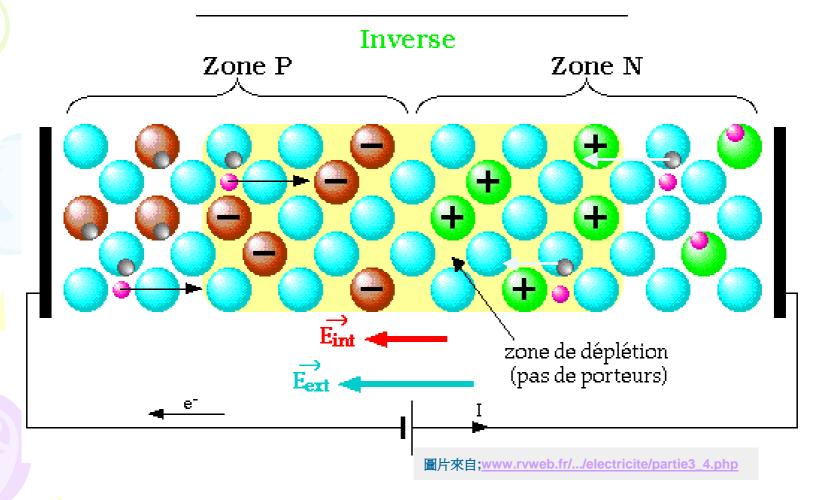
 \mathcal{E}_s : Silicon Electrical permirrivity 容電係數

For silicon

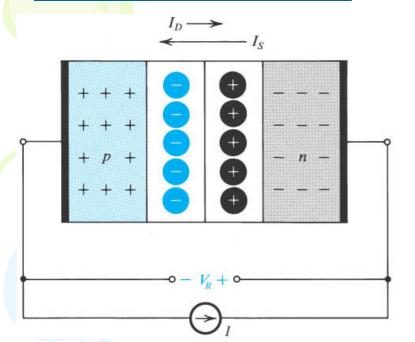
$$\varepsilon_s = 1.04 \times 10^{-12} F/cm$$

$$W_{dep} = 0.1 \mu m \sim 1 \mu m$$

Jonction PN avec champ extérieur



PN Junction reverse bias



$$I_{S} > I_{D}$$

$$I_{S} - I_{D} = I$$

$$q_{J} = q_{N} = qN_{D}W_{n}A$$

$$q_{J} = q \frac{N_{A}N_{D}}{N_{A} + N_{D}}AW_{dep}$$

$$W_{dep} = W_n + W_p = \sqrt{\frac{2\varepsilon_s}{q}(\frac{1}{N_A} + \frac{1}{N_D})(V_0 + V_R)}$$

 $C_{j} = \frac{C_{jo}}{\sqrt{1 + \frac{V_{R}}{V}}} \quad \text{varactor}$

Junction capacitance

$$C_{j} = \frac{dq_{J}}{dV_{R}} \Big|_{V_{R} = V_{Q}}$$

$$\Rightarrow C_{j} = \frac{\varepsilon_{s} A}{W_{dep}}$$

2006

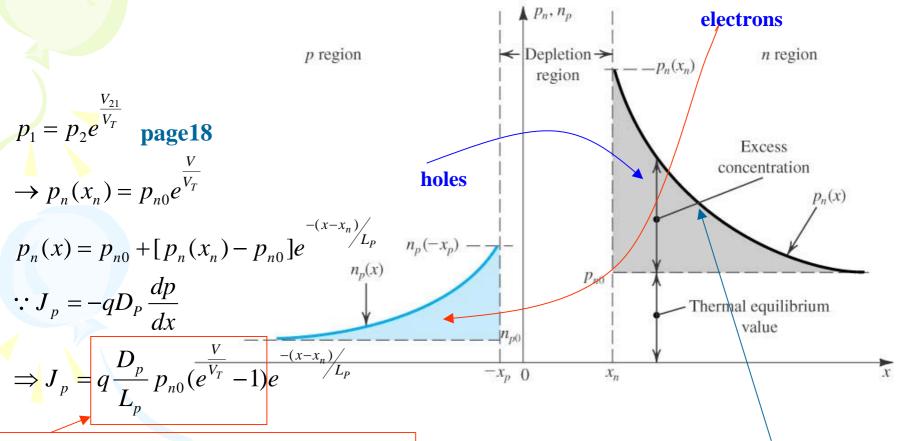
$$C_{jo} = A\sqrt{\frac{q\varepsilon_s}{2}(\frac{N_A N_D}{N_A + N_D})\frac{1}{V_0}}$$

$$V_R = 0$$

Jonction PN avec champ extérieur

Direct Zone P Zone N 圖片來自;www.rvweb.fr/.../electricite/partie3_4.php

Minority carriers distribution in forward bias (the story about reverse saturation current)

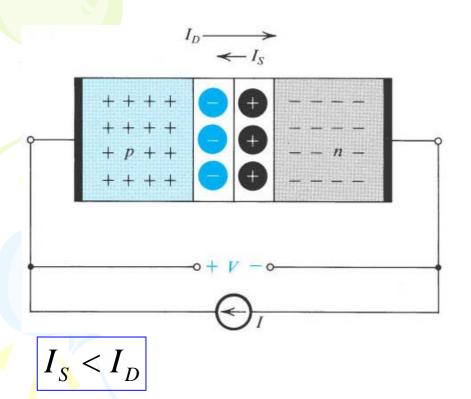


Total loss by recombination

= External electric field inject electrons

Inject holes from P region to diffuse away from the junction into the N region and disappear by recombination

PN Junction under forward bias



$$J_{p} = q \frac{D_{p}}{L_{p}} p_{no} (e^{\frac{V}{V_{T}}} - 1)$$

$$J_{n} = q \frac{D_{n}}{L_{n}} n_{po} (e^{\frac{V}{V_{T}}} - 1)$$

$$I = A(J_p + J_n)$$

$$I = Aqn_i^2 \left(\frac{D_p}{L_p N_D} + \frac{D_p}{L_p N_D}\right) (e^{\frac{V}{V_T}} - 1)$$

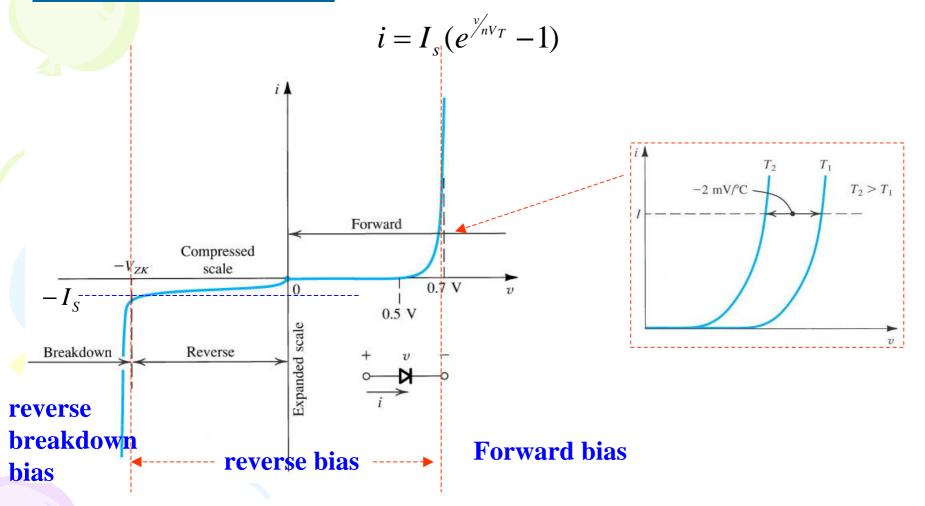
2006

$$I = I_s \left(e^{V/V_T} - 1 \right)$$
if $V << 0$

$$I_s = Aqn_i^2 \left(\frac{D_n}{L_n N_A} + \frac{D_p}{L_p N_D} \right)$$

$$I = I_s(e^{v/v_T} - 1)$$

Diode's i-v relationship



n = 1,2 Ideality factor which depending on diode's material and physical structure

Forward bias

$$i = I_s(e^{\frac{y}{nV_T}} - 1)$$

$$i \gg I_s$$
 Forward

$$\Rightarrow i \approx I_s e^{\frac{v}{nV_T}}$$

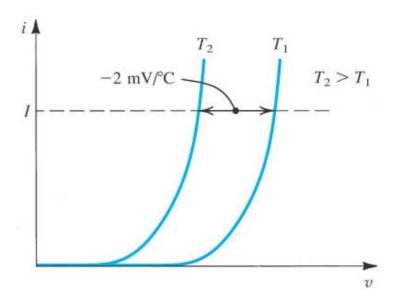
$$\Rightarrow v = nV_T \ln \frac{i}{I_s}$$

$$I_1 \approx I_s e^{\frac{V_1}{nV_T}}$$

$$I_2 \approx I_s e^{\frac{V_2}{nV_T}}$$

$$I_2 \approx I_s e^{\frac{V_2}{nV_T}}$$

$$\Rightarrow V_2 - V_1 = nV_T \ln \frac{I_2}{I_1} = 2.3nV_T \log \frac{I_2}{I_1}$$



n: Ideality factor which depending on diode's material and physical structure

$$n = \begin{cases} 1 & Ge \\ 1 & Si(I_D \ge 25mA) \\ 2 & Si(I_D \le 25mA) \end{cases}$$

Open current
$$\longrightarrow V_D = 0 \Rightarrow I_D = 0$$

Forward bias
$$V_D > 0 \Rightarrow I_D \approx I_s e^{\frac{V_D}{nV_T}}$$

reverse bias
$$V_D < 0 \Rightarrow I_D = -I_s$$

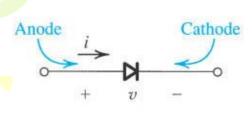
<u>Cut-in voltage</u> V_r

$$V_r = 0.7 \rightarrow Si$$

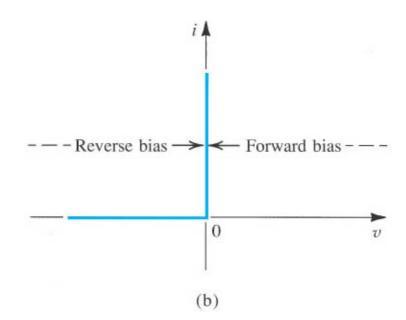
$$V_r = 0.25 \rightarrow Ge$$

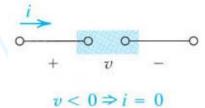
$$V_r = 1.2 \rightarrow GaAs$$

Diode Model I (ideal model)

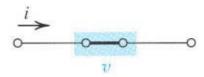


(a)





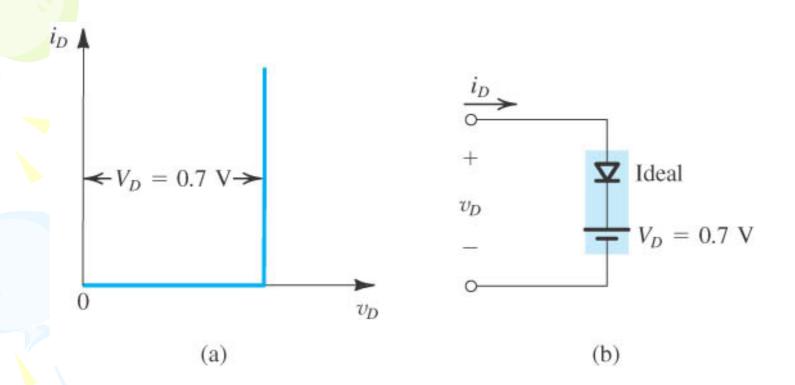
(c)



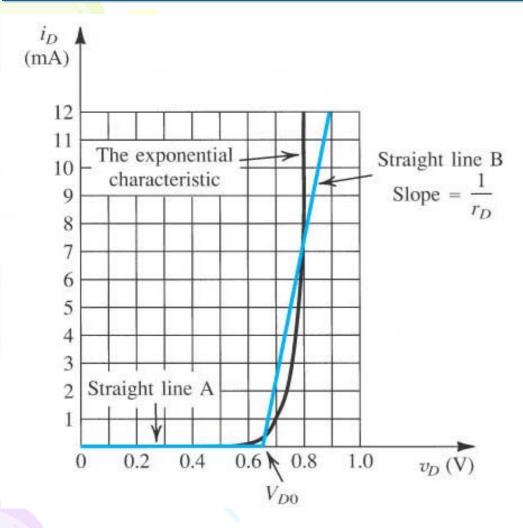
$$i > 0 \Rightarrow v = 0$$

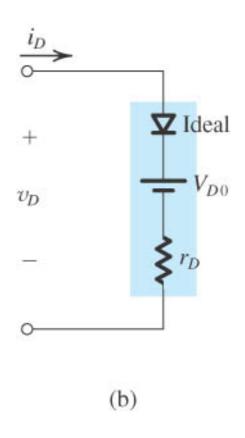
(d)

Diode Model II (constant-Voltage Drop model)



Diode Model III (Piecewise-linear model)





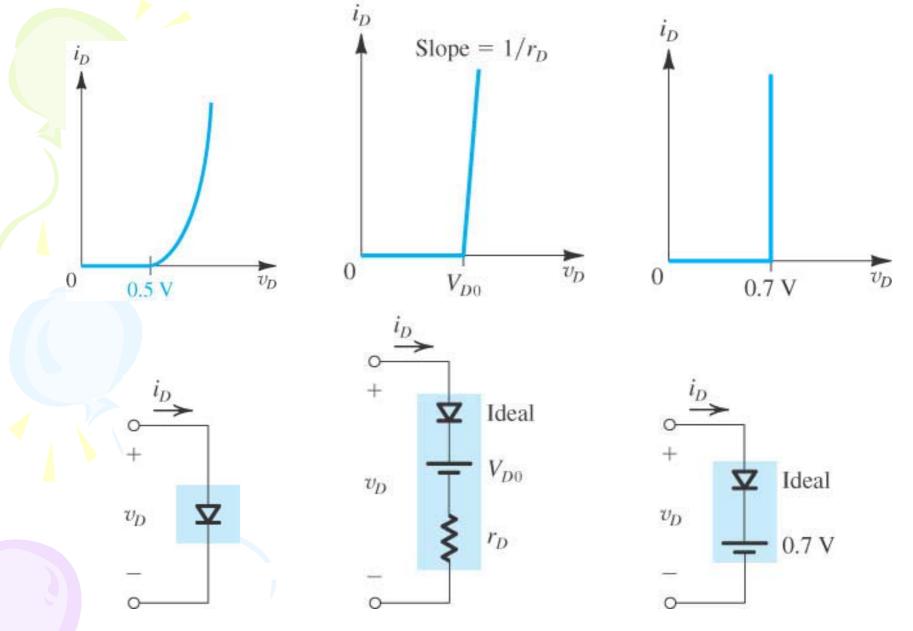
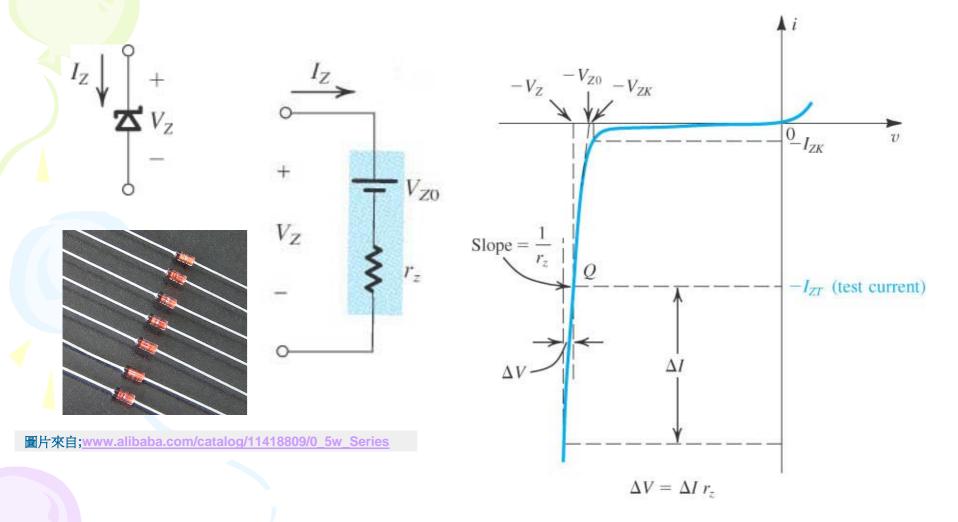
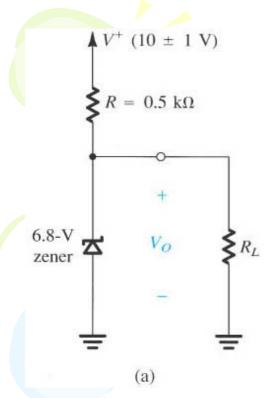
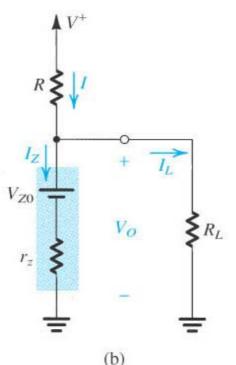


Table 3.1 Modeling the Diode Forward Characteristic

Special Diodes (Zener Diode)







$$I = I_z + I_L$$

$$\Rightarrow \frac{V - V_z}{R} = \frac{P_z}{V_z} + \frac{V_z}{R_L}$$

$$I = I_{z(\text{max})} + I_{L(\text{min})}$$

$$\Rightarrow \frac{V - V_z}{R} = \frac{P_{z(\text{max})}}{V_z} + \frac{V_z}{R_{L(\text{max})}}$$

$$I = I_{z(\min)} + I_{L(\max)}$$

$$\Rightarrow \frac{V - V_z}{R} = \frac{P_{z(\min)}}{V_z} + \frac{V_z}{R_{L(\min)}}$$

Ideal case: $r_z = 0$

$$R_L \uparrow (\max) \rightarrow I_L \downarrow :: R = K :: I = fixed \Rightarrow I_z \uparrow (\max)$$

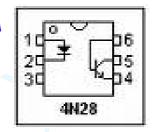
$$R_L \downarrow (\min) \rightarrow I_L \uparrow :: R = K :: I = fixed \Rightarrow I_z \downarrow (\min)$$

The others Special Diodes

- 1. Schottky Diode
 - Metal + semiconductor (unipolar)

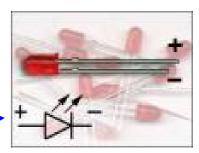


- GaAs diode
- GaN diode (B, G)
- 3. Tunnel diode
- 4. Photo diode (PD)-----
- 5. Opto coupler (LED + PD)



www.du.edu/~etuttle/electron/circ43.gif





www.personeel.glr.nl/koster/elektro/ledjes.JPG



hyperphysics.phy-astr.gsu.edu/.../tundio.html



home.swipnet.se/.../hifi_100pr/photodiode.jpg



www.geda.seul.org/.../analog/photodiode-1_tn.png

LED

- 1963 Red
 - 1993 Blue
 - 1996 white